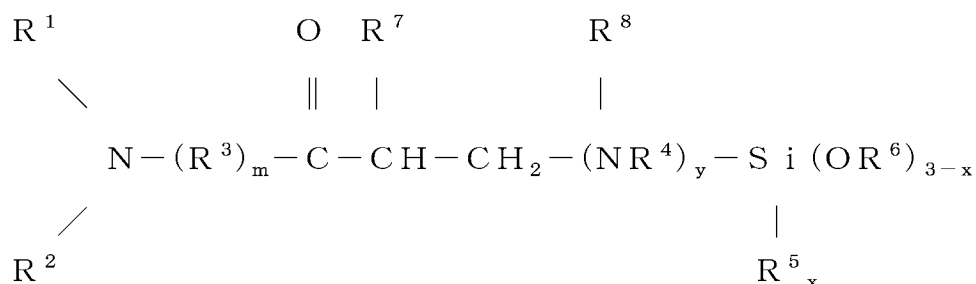


IN THE CLAIMS:

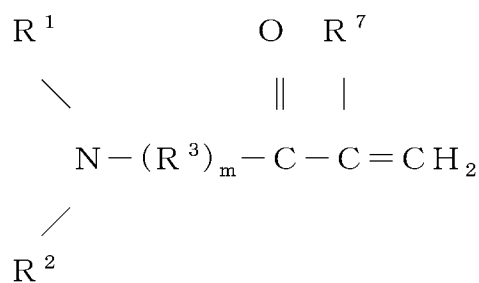
1. (Original) A nitrogen-containing organosilicon compound of the formula:



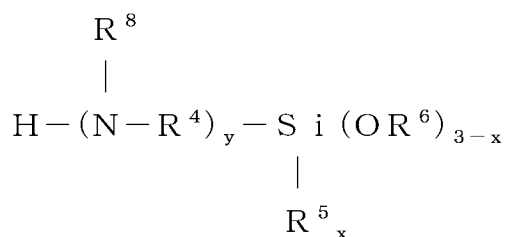
wherein R¹ and R² are the same or different univalent hydrocarbon groups with 1-15 carbon atoms; R³ is a bivalent hydrocarbon group with 1-15 carbon atoms, or an alkyleneoxy group of the formula -C_nH_{2n}O- where n is 1-15; R⁴ is a bivalent hydrocarbon group with 1-15 carbon atoms; R⁵ is a univalent hydrocarbon group with 1-15 carbon atoms; R⁶ is a univalent hydrocarbon group with 1-15 carbon atoms or an alkoxyalkyl group; R⁷ is an alkyl group or a hydrogen atom; R⁸ is a hydrogen atom, an alkyl group with 1-20 carbon atoms, or an aryl group; m is 0 or 1; x is 0-2; and y is 1-5.

2. (Cancelled).

3. (Withdrawn) A method of manufacturing a nitrogen-containing organosilicon compound comprising the addition reaction of a compound of the formula;



and a compound of the formula:



wherein R¹ and R² are the same or different univalent hydrocarbon groups with 1-15 carbon atoms; R³ is a bivalent hydrocarbon group with 1-15 carbon atoms, or an alkyleneoxy group of the formula -C_nH_{2n}O- where n is 1-15; R⁴ is a bivalent hydrocarbon group with 1-15 carbon atoms; R⁵ is a univalent hydrocarbon group with 1-15 carbon atoms; R⁶ is a univalent hydrocarbon group with 1-15 carbon atoms or an alkoxyalkyl group; R⁷ is an alkyl group or a hydrogen atom; R⁸ is a hydrogen atom, an alkyl group with 1-20 carbon atoms, or an aryl group; m is 0 or 1; x is 0-2; and y is 1-5.

4. (Previously Presented) A method of manufacturing the nitrogen-containing organosilicon compound defined in Claim 1.

5. (Cancelled).

6. (Cancelled).

7. (Withdrawn)A method of treating a surface comprising applying to the surface a nitrogen-containing organosilicon compound according to Claim 1.

8. (Cancelled).

9. (Withdrawn)A method of treating a surface comprising applying to the surface a solution containing the nitrogen-containing organosilicon compound according to Claim 1.

10. (Cancelled).